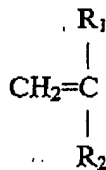


CLAIM AMENDMENTS

~~1. (Currently Amended) A nail enamel composition comprising, by weight of the total composition:~~

10-95% solvent, and

5-95% of a polymer capable of forming a film on the nail, having a glass transition temperature in the range of 5 to 90° C., obtained by polymerizing at least two different types of monomers wherein one monomer is a nonpolar ethylenically unsaturated monomer and the other monomer is a polar monomer of the formula:



wherein R₁ is H, or a C₁₋₃₀ straight or branched chain alkyl, aryl, or aralkyl; and R₂ is COOM wherein M is H; (CHR₁)_nOH; (CH₂CH₂O)_nH; (CH₂)_nNR₁; (CHR₁CONR₁H) where n is 1-100, and wherein the polar monomer is present at about 2 to 29% by weight of the total polymer; wherein said polymer is substantially free of monomers containing acetoacetoxy moieties.

~~2. (Original) The composition of claim 1 wherein the solvent is aqueous.~~

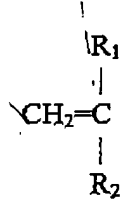
~~3. (Original) The composition of claim 1 wherein the comprises a non-aqueous solvent.~~

~~4. (Original) The composition of claim 3 wherein the non-aqueous solvent is an aliphatic or aromatic ketone; aliphatic or aromatic alcohol; glycol ether; ester, or mixtures thereof.~~

5. (Original) The composition of claim 1 wherein the film forming polymer the polar monomer is anionically or cationically charged.

6. (Original) The composition of claim 5 wherein the polar monomer is anionically charged.

7. (Original) The composition of claim 6 wherein the polar monomer has the general formula:



wherein R_1 is H, or a C_{1-30} straight or branched chain alkyl, aryl, or aralkyl; and R_2 is COOM wherein M is H; $(CR_1)_nOH$; $(CH_2CH_2O)_nH$, $(CH_2)_nNR_1$; where n is 1-100.

8. (Original) The composition of claim 7 wherein the polar monomer, R_1 is H or CH_3 , and R_2 is COOM wherein M is H.

9. (Original) The composition of claim 8 wherein the polar monomer is acrylic acid.

10. (Original) The composition of claim 1 further comprising 0.1-30% by weight of the total composition of pigment.

11. (Original) The composition of claim 1 further comprising 0.01-15% by weight of the total composition of a suspending agent.

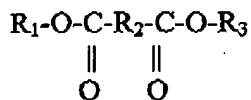
12. (Original) The composition of claim 11 wherein the suspending agent is a montmorillonite mineral or associative thickener.

13. (Original) The composition of claim 1 further comprising 0.01-10% by weight of the total composition of a silicone glycol copolymer defoaming agent.

14. (Original) The composition of claim 1 further comprising 0.1-35% by weight of the total composition of one or more plasticizers.

15. (Original) The composition of claim 14 wherein the plasticizer comprises a glyceryl, glycol, or citrate ester.

16. (Original) The composition of claim 14 wherein the plasticizers comprises a compound of the general formula:



wherein R₁, R₂, and R₃ are each independently a C₁₋₂₀ straight or branched chain alkyl or alkylene which may be substituted with one or more hydroxyl groups.

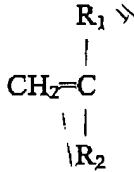
17. (Currently Amended) A two container kit for polishing nails comprising:

(a) a first container containing a nail enamel composition comprising, by weight of the total composition:

10-95% solvent, and

5-95% of a film forming polymer having a glass transition temperature in the range of 5 to 90° C. obtained by polymerizing at least two different types of monomers wherein one

monomer is a nonpolar ethyl nically unsaturated monomer and the other monomer is a polar monomer of the formula:



wherein R_1 is H, or a C_{1-30} straight or branched chain alkyl, aryl, or aralkyl; and R_2 is COOM wherein M is H; $(CHR_1)_nOH$; $(CH_2CH_2O)_nH$; $(CH_2)_nNR_1$; (CHR_1CONR_1H) where n is 1-100, and wherein the polar monomer is present at about 2 to 29% by weight of the total polymer;

wherein said polymer is substantially-free of monomers containing acetoacetoxy moieties; and

(b) a second container containing a nail enamel topcoat composition comprising, by weight of the total topcoat composition:

1-99% solvent, and

1-99% of a film forming polymer.

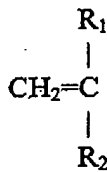
~~18. (Currently Amended) The kit of claim 17 wherein the film forming polymer in the second container comprises a cellulosic based film former.~~

~~19. (Currently Amended) A method for polishing the nails comprising:~~

(a) applying to the nails a first composition comprising, by weight of the total composition:

10-95% solvent, and

5-95% of a film forming polymer having a glass transition temperature in the range of 5 to 90° C. obtained by polymerizing at least two different types of monomers wherein one monomer is a nonpolar ethylenically unsaturated monomer and the other monomer is a polar monomer of the formula:



C₂ wherein R₁ is H, or a C₁₋₃₀ straight or branched chain alkyl, aryl, or aralkyl; and R₂ is COOM wherein M is H; (CHR₁)_nOH; (CH₂CH₂O)_nH, (CH₂)_nNR₁; (CHR₁CONR₁H) where n is 1-100, and wherein the polar monomer is present at about 2 to 29% by weight of the total polymer; and wherein said polymer is substantially free of monomers containing acetoacetoxy moieties; and

(b) applying to the nails a second composition comprising, by weight of the total composition:

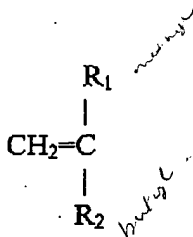
1-99% solvent, and

1-99% of a film forming polymer; wherein the dried film formed by (a) and (b)

resides on the nails for five to ten days.

20. Cancelled.

~~21. (Previously Added)~~ The composition of claim 1 wherein the ethylenically unsaturated nonpolar monomer is a monofunctional monomer having the formula:



wherein R₁ is H, a C₁₋₃₀ straight or branched chain alkyl, aryl, aralkyl; R₂ is H, CH₃, a pyrrolidone, or a substituted or unsubstituted aromatic, alicyclic, or bicyclic ring where the substituents are C₁₋₃₀ straight or branched chain alkyl, or COOM wherein M is a C₁₋₃₀ straight or branched chain alkyl, pyrrolidone, or a substituted or unsubstituted aromatic, alicyclic, or bicyclic ring where the substituents are C₁₋₃₀ straight or branched chain alkyl which may be substituted with one or more halogens.

~~22.~~ **(Currently Amended)** The composition of claim ~~22~~ 21 wherein R₁ in the nonpolar monomer is H or a C₁₋₃₀ straight or branched chain alkyl, and R₂ in the nonpolar monomer is COOM wherein M is a C₁₋₃₀ straight or branched chain alkyl.

~~23.~~ **(Previously Added)** The composition of claim 22 wherein R₁ in the nonpolar monomer is H or methyl and R₂ in the nonpolar monomer is COOM wherein M is a C₁₋₄ alkyl.

~~24.~~ **(Previously Added)** The composition of claim 22 wherein R₁ is methyl and R₂ is COOM wherein M is butyl and the monomer is butyl methacrylate.

~~25.~~ **(Previously Added)** The composition of claim 24 wherein the polar monomer R₁ is H or methyl, and R₂ is COOM wherein M is H.

~~26.~~ **(Previously Added)** The composition of claim 24 wherein the polar monomer is acrylic acid or methacrylic acid.

~~27. (Previously Added) The composition of claim 1 wherein the polymer consists of a nonpolar monomer which is butyl methacrylate and a polar monomer which is acrylic acid and the acrylic acid is present at about 2-29% by weight of the total polymer.~~

~~28. (New) A nail enamel composition comprising, by weight of the total composition:~~

~~10-95% solvent, and~~

~~5-95% of a copolymer capable of forming a film on the nail, having a glass transition temperature in the range of 5 to 90° C., and consisting of butyl methacrylate copolymerized with a polar monomer selected from the group consisting of acrylic acid, methacrylic acid, and mixtures thereof.~~

~~29. (New) The composition of claim 28 wherein the copolymer consists of 2-29% by weight of the total copolymer of acrylic acid, with the remainder of the copolymer being butyl methacrylate.~~

~~30. (New) The composition of claim 28 wherein the copolymer consists of 2-29% by weight of the total polymer of methacrylic acid, with the remainder of the copolymer being butyl methacrylate.~~

~~31. (New) A nail enamel composition comprising, by weight of the total composition:~~

~~10-95% solvent, and~~

~~5-95% of a copolymer capable of forming a film on the nail, having a glass transition temperature in the range of 5 to 90° C., and consisting of methyl methacrylate polymerized with a~~

polar monomer selected from the group consisting of acrylic acid, methacrylic acid, and mixtures thereof.

~~32.~~ (New) The nail enamel composition of claim 31 wherein the copolymer consists of 2-29% by weight of the total polymer of acrylic acid, with the remainder of the copolymer being methyl methacrylate.

~~33.~~ (New) A nail enamel composition comprising, by weight of the total composition:

10-95% solvent, and

5-95% of a copolymer capable of forming a film on the nail, having a glass transition temperature in the range of 5 to 90° C., and consisting of a nonpolar monomer selected from the group consisting of methyl methacrylate, butyl methacrylate, and mixtures thereof; polymerized with a polar monomer selected from the group consisting of acrylic acid, methacrylic acid, and mixtures thereof.

~~34.~~ (New) The composition of claim 33 wherein the copolymer consists of 2-29% of a polar monomer selected from the group consisting of acrylic acid, methacrylic acid, and mixtures thereof, with the remainder of the copolymer being a nonpolar monomer selected from the group consisting of butyl methacrylate, methyl methacrylate, and mixtures thereof.

~~35.~~ (New) A method for polishing the nails comprising:

(a) applying to the nails a first composition comprising, by weight of the total composition:

10-95% solvent, and

5-95% of a film forming polymer having a glass transition temperature in the range of 5 to 90° C., and consisting of a nonpolar monomer selected from the group consisting of methyl methacrylate, butyl methacrylate, and mixtures thereof; copolymerized with a polar monomer selected from the group consisting of acrylic acid, methacrylic acid, and mixtures thereof.

C₅ (b) applying to the nails a second composition comprising, by weight of the total composition:

1-99% solvent, and

1-99% of a cellulose film forming polymer; wherein the dried film formed by (a) and (b)

resides on the nails for five to ten days.

~~36.~~ (New) The method of claim 35 wherein the cellulose film forming polymer comprises nitrocellulose.
